

*Amendments to the Specification*

Please replace paragraph [0046] with the following amended paragraph:

The exemplary patterns are: (1) an annular apodization blocking a portion of the zero order lobe of the pixel diffraction pattern; (2) a semi-plane, or a single edge apodization function (knife edge); (3) a shearing grating or diffraction grating apodization function; (4) shearing of the field in the image plane allowing to use shearing interferometry for the SLM calibration can be achieved utilizing many physical arrangements other than a shearing grating, known to those skilled in the art (e.g., beam dividers, special prisms or mirrors can be used); (5) lateral shearing interferometry, for example as is described in U.S. Ser. No. ~~10/~~10/765,947 entitled "System And Method For Pistoning A Micromirror Spatial Light Modulator Array Using Shearing Interferometry," filed 01/29/2004, now U.S. Patent No. 6,847,461 (~~Atty.~~ ~~1857.2270000~~), which is incorporated herein by reference in its entirety; and (6) a more general apodization function resulting from the computational, analytical or ad-hoc solution of the constrained optimization problem (based on the principal requirements to an entrance pupil apodization function), which can include the variations in both transmittance and phase or the apodization function may include only the phase variation (e.g. a phase shear grating, or an edge alternating the phase by  $\pi$ ).